| L Number | Hits | Search Text | DB | Time stamp |
|-------------|------|--|---------------------|------------|
| 1 | 44 | (tft or (thin near film near transistor)) with | USPAT; | 2004/09/14 |
| | | (insulating or dielectric) with gate with | US-PGPUB; | 11:38 |
| | | electrode with (semiconductor adj layer) | EPO; JPO; | |
| | | with (source or drain or source/drain) with | DERWENT; | |
| | | (passivation or passivating or protective) | IBM_TDB | |
| | | with (porous or amorphous or pore or | | |
| | | porosity) | | |
| 2 | 8 | ((tft or (thin near film near transistor)) with | USPAT; | 2004/09/14 |
| | | (insulating or dielectric) with gate with | US-PGPUB; | 11:41 |
| | | electrode with (semiconductor adj layer) | EPO; JPO; | |
| | | with (source or drain or source/drain) with | DERWENT; | |
| | | (passivation or passivating or protective) | IBM_TDB | |
| | | with (porous or amorphous or pore or | | |
| | | porosity)).ti,ab,clm. | | |
| 3 | 2 | ((tft or (thin near film near transistor)) with | USPAT; | 2004/09/14 |
| | | (insulating or dielectric) with gate with | US-PGPUB; | 11:41 |
| | | electrode with (semiconductor adj layer) | EPO; JPO; | |
| | | with (source or drain or source/drain) with | DERWENT; | |
| | | (passivation or passivating or protective) | IBM_TDB | |
| | | with (porous or amorphous or pore or | | |
| | | porosity) with (charge or ion or | | |
| | | implantation or impurity)).ti,ab,clm. | | |
| 4 | 1 | ((tft or (thin near film near transistor)) with | USPAT; | 2004/09/14 |
| | | (insulating or dielectric) with gate with | US-PGPUB; | 11:43 |
| | | electrode with (semiconductor adj layer) | EPO; JPO; | |
| | | with (source or drain or source/drain) with | DERWENT; | |
| | | (passivation or passivating or protective) | IBM_TDB | |
| | | with (porous or amorphous or pore or | | |
| | | porosity)).ti,ab,clm. and ((amorphous or | | |
| | | pore or porous or porosity) near5 | | |
| | | (semiconductor adj layer) near5 (charge or | | |
| _ | | impurity or ion or doping)) | | 0004/00/44 |
| 5 | 8 | ((tft or (thin near film near transistor)) with | USPAT; | 2004/09/14 |
| | | (insulating or dielectric) with gate with | US-PGPUB; | 11:43 |
| | | electrode with (semiconductor adj layer) | EPO; JPO; | |
| | | with (source or drain or source/drain) with (passivation or passivating or protective) | DERWENT; IBM_TDB | |
| | | with (porous or amorphous or protective) | IDM_IDD | |
| | | porosity)).ti,ab,clm. | | |
| 6 | 6 | ((tft or (thin near film near transistor)) with | USPAT; | 2004/09/14 |
| | • | (insulating or dielectric) with gate with | US-PGPUB; | 11:45 |
| | | electrode with (semiconductor adj layer) | EPO; JPO; | |
| | | with (source or drain or source/drain) with | DERWENT; | |
| | | (passivation or passivating or protective) | IBM_TDB | |
| | | with (porous or amorphous or pore or | | |
| | | porosity)) and ((amorphous or pore or | | |
| | | porous or porosity) near5 (semiconductor | | |
| | | adj layer) near5 (charge or impurity or ion | | |
| | | or doping)) | | |

| 7 | 6 | ((tft or (thin near film near transistor)) with | USPAT; | 2004/09/14 |
|----|---|---|-----------|------------|
| - | | (insulating or dielectric) with gate with | US-PGPUB; | 11:45 |
| | | electrode with (semiconductor adj layer) | EPO; JPO; | |
| | | with (source or drain or source/drain) with | DERWENT; | |
| | | (passivation or passivating or protective) | IBM_TDB | |
| | | with (porous or amorphous or pore or | _ | |
| | | porosity)) and ((amorphous or pore or | | |
| | | porous or porosity) near5 (semiconductor | • | |
| | | adj layer) near5 (passivation or protective)) | | |
| 8 | 4 | ((tft or (thin near film near transistor)) with | USPAT; | 2004/09/14 |
| | - | (insulating or dielectric) with gate with | US-PGPUB; | 11:47 |
| | | electrode with (semiconductor adj layer) | EPO; JPO; | |
| | | with (source or drain or source/drain) with | DERWENT; | |
| | | (passivation or passivating or protective) | IBM_TDB | |
| | | with (porous or amorphous or pore or | IBM_IBB | |
| | | porosity)) and ((amorphous or pore or | : | |
| | | porous or porosity) near3 (semiconductor | | |
| 40 | | - • | | |
| | | adj layer) near3 (passivation or protective)) | LICDAT. | 2004/09/14 |
| 10 | 1 | ((tft or (thin near film near transistor)) with | USPAT; | |
| | | (insulating or dielectric) with gate with | US-PGPUB; | 11:48 |
| | | electrode with (semiconductor adj layer) | EPO; JPO; | , |
| | | with (source or drain or source/drain) with | DERWENT; | |
| | | (passivation or passivating or protective) | IBM_TDB | |
| | | with (porous or amorphous or pore or | | |
| | | porosity)).clm. and ((amorphous or pore or | | |
| | | porous or porosity) near5 (semiconductor | | |
| | | adj layer) near5 (passivation or | | |
| | | protective)).clm. | | |
| 9 | 2 | ((tft or (thin near film near transistor)) with | USPAT; | 2004/09/14 |
| | | (insulating or dielectric) with gate with | US-PGPUB; | 11:48 |
| | | electrode with (semiconductor adj layer) | EPO; JPO; | |
| | | with (source or drain or source/drain) with | DERWENT; | |
| | | (passivation or passivating or protective) | IBM_TDB | |
| | | with (porous or amorphous or pore or | | |
| | | porosity)) and ((amorphous or pore or | | |
| | | porous or porosity) near5 (semiconductor | | |
| | | adj layer) near5 (passivation or | | |
| | | protective)).clm. | | |
| 11 | 2 | ((tft or (thin near film near transistor)) with | USPAT; | 2004/09/14 |
| | | (insulating or dielectric) with gate with | US-PGPUB; | 11:49 |
| | | electrode with (semiconductor adj layer) | EPO; JPO; | |
| | | with (source or drain or source/drain) with | DERWENT; | |
| | | (passivation or passivating or protective) | IBM_TDB | |
| | | with (porous or amorphous or pore or | | |
| | | porosity)).clm. | | |